Electronic Supplementary Material (ESI) for RSC Advances.

Supplementary Information for the manuscript: *High quality sub-10 nm graphene nanoribbons by on-chip PS-b-PDMS block copolymer lithography*, **by Rasappa *et.al.***

1. SEM image shows the confinement of graphene nanoribbons inside the SU-8 trenches.
2. Raman Intensity map showing the spatial homogeneity of graphene nanoribbons after etching.

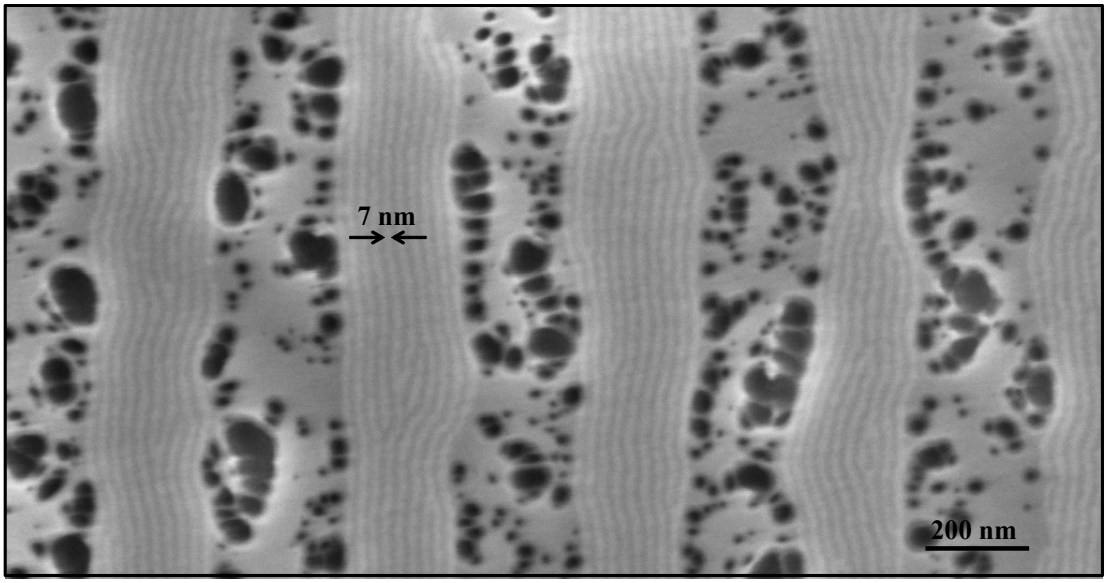

Figure SI.1: Confinement of graphene nanoribbons inside SU-8 trenches.

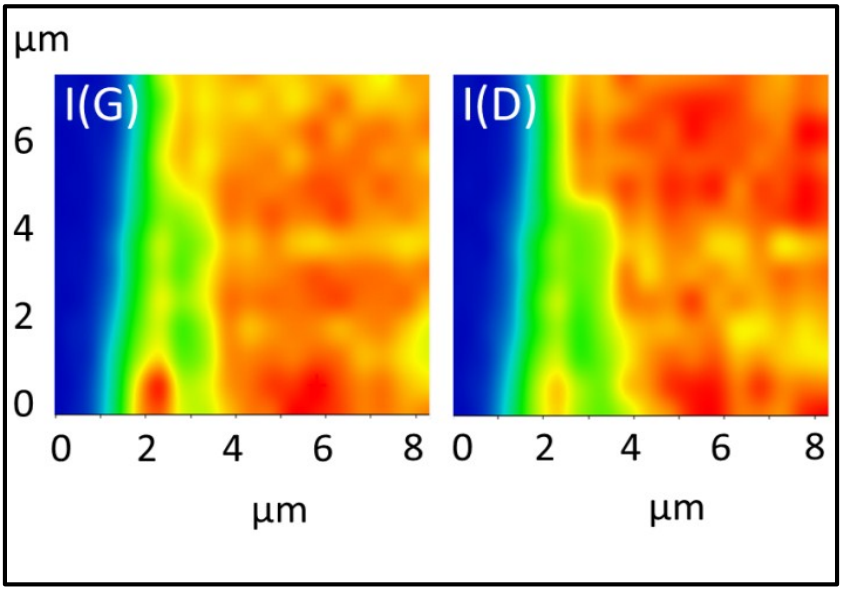

Figure SI.2: Raman maps of I(G) and I(D) of graphene nanoribbons showing the spatial homogeneity of the ribbon width during the etching process of graphene. The ratio of both values is ~ 1 in all the positions, indicating the homogeneity achieved in the process. The spatial separation between the taken spectra is 0.5 µm in both directions.